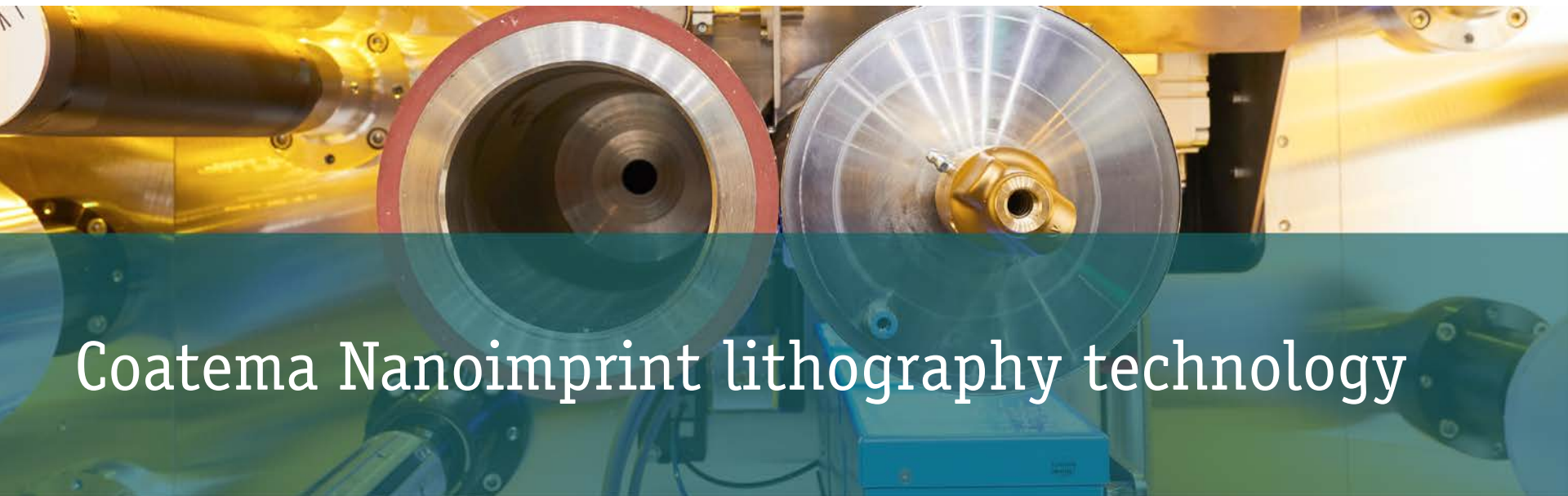




Coatema Nanoimprint lithography technology

Summary

Introduction

Technologies
and processes

Products

Equipment

Summary

Summary

Introduction

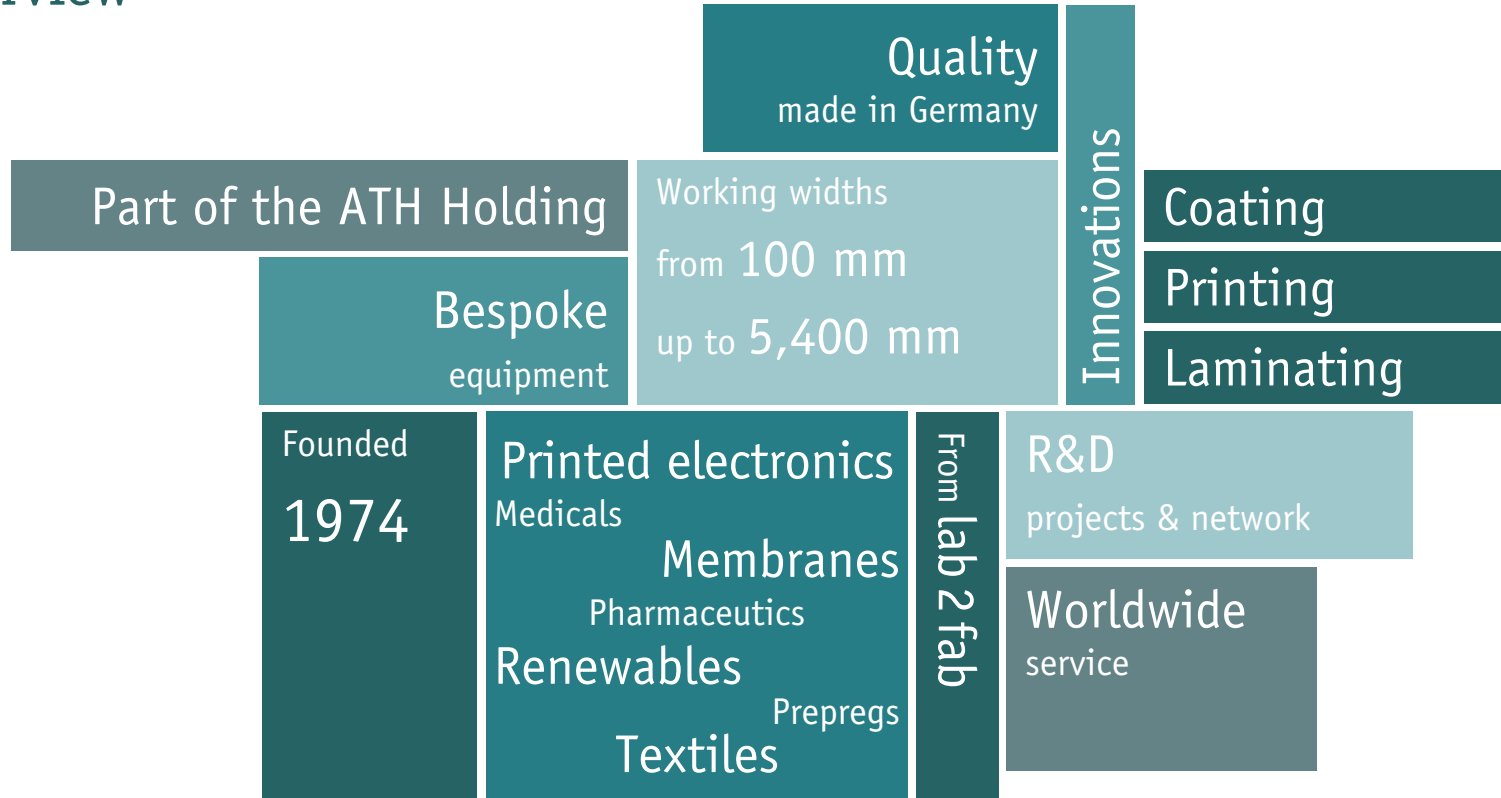
Technologies
and processes

Products

Equipment

Summary

Overview



Group of companies

ATH ALTONAER
TECHNOLOGIE
HOLDING



- ✓ Founded 1903
- ✓ Approx. 200 employees
- ✓ Located in Hamburg



- ✓ Founded 1995
- ✓ Approx. 50 employees
- ✓ Located in Norderstedt



- ✓ Founded 1974
- ✓ Approx. 50 employees
- ✓ Located in Dormagen

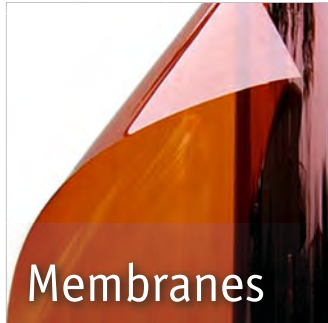
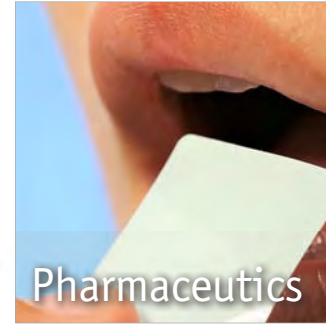
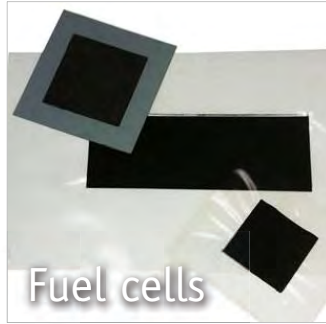


- ✓ Founded 1919
- ✓ Approx. 140 employees
- ✓ Located in Hamburg

Represented worldwide



Our markets



Our work in associations – global networking



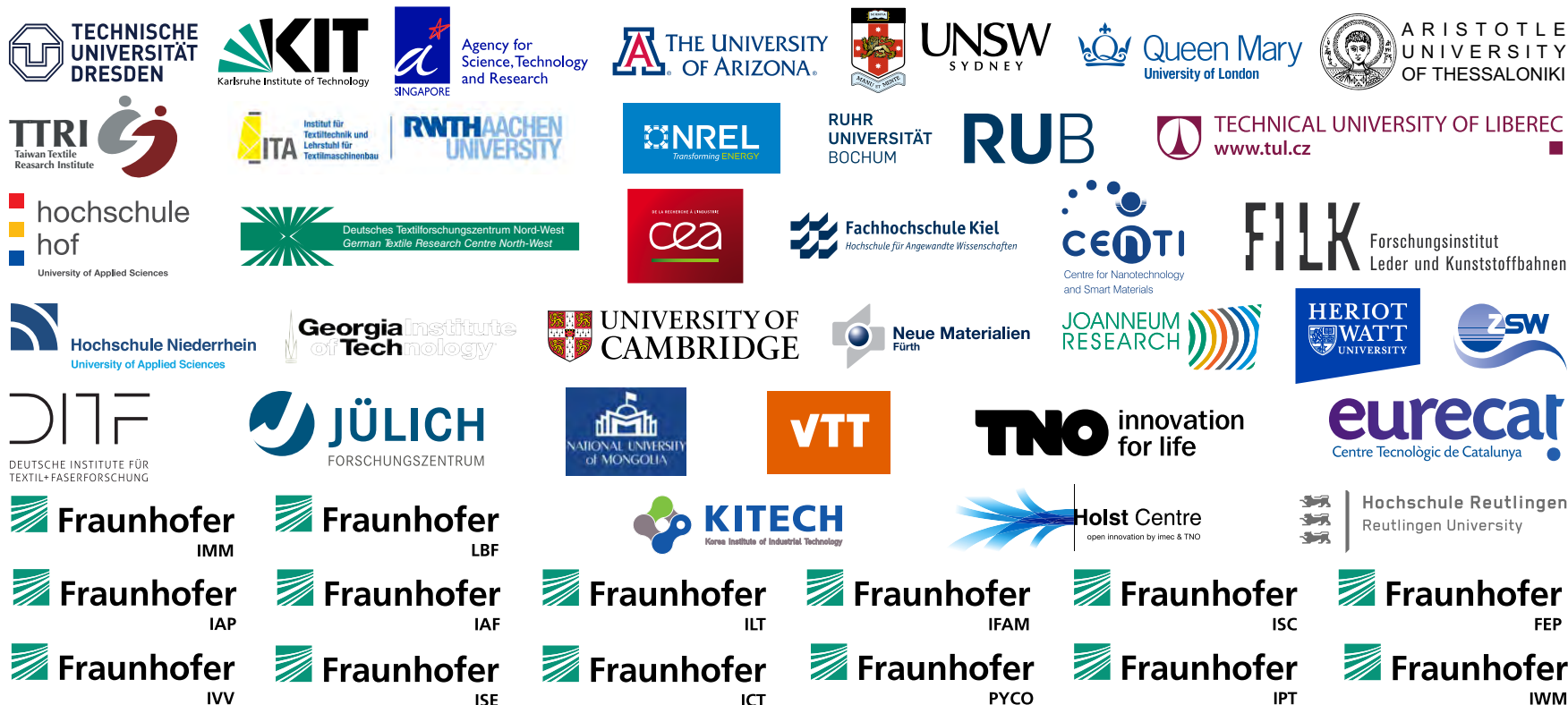
Board Member:
OE-A

Advisory Board:
Fraunhofer ITA

Coatema customers



R&D customers



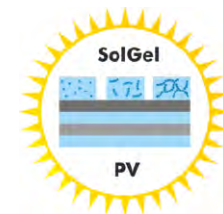
R&D projects overview 2020



Oled Solar



E-Nanoprint Pro



Summary

Introduction

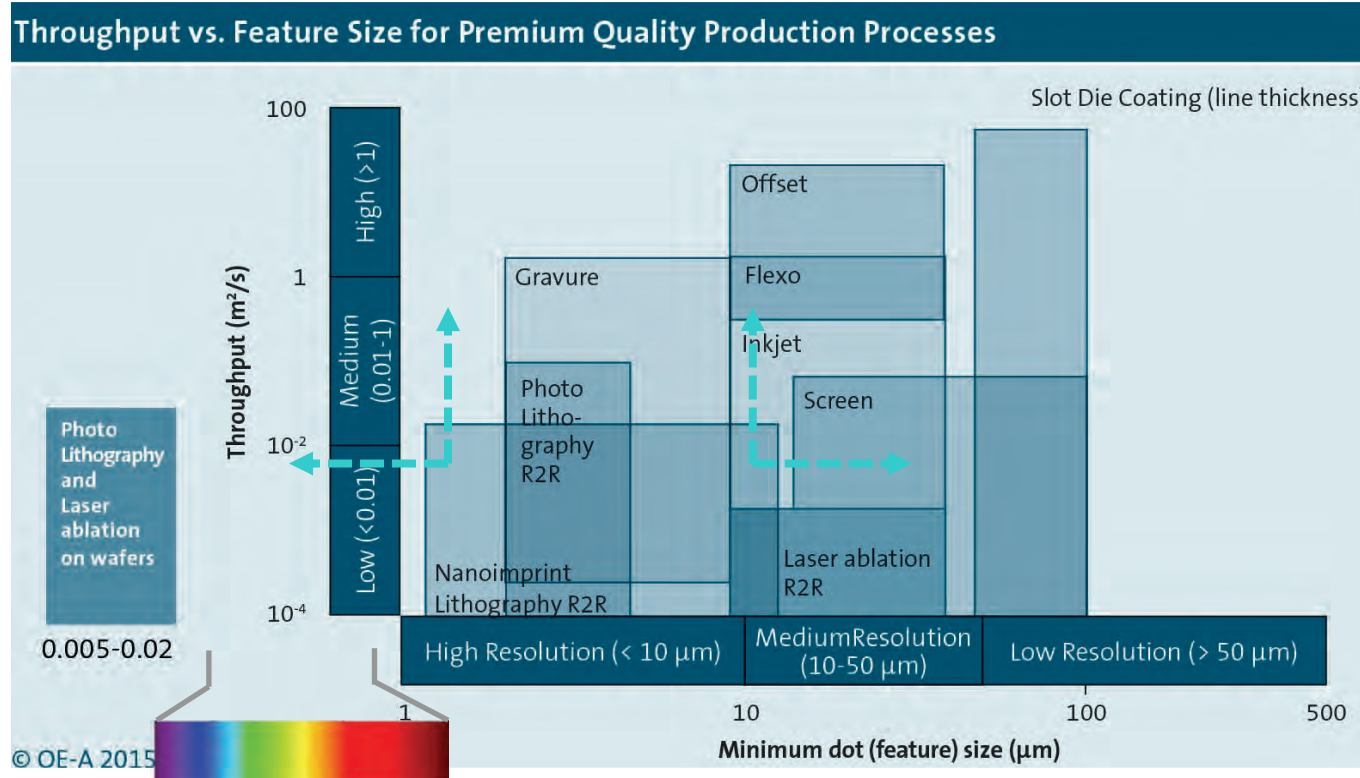
Technologies
and processes

Products

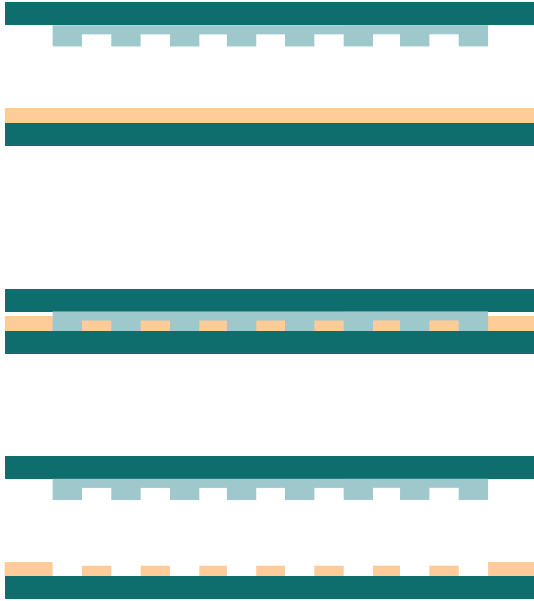
Equipment

Summary

Why is nanoimprint lithography relevant?



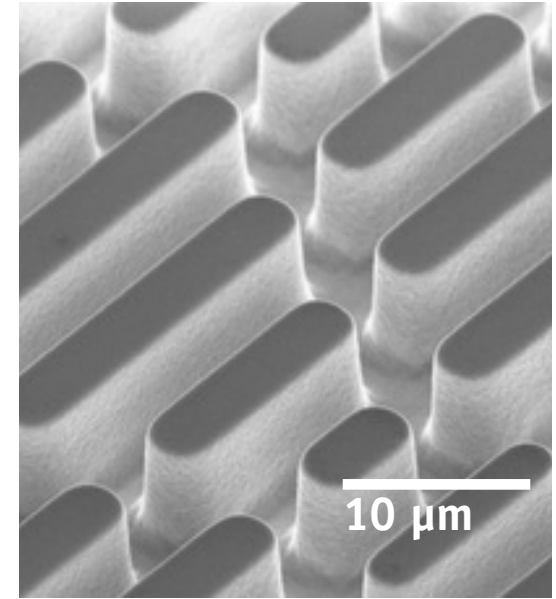
Basic principle of nanoimprint lithography



Principle



Ancient days

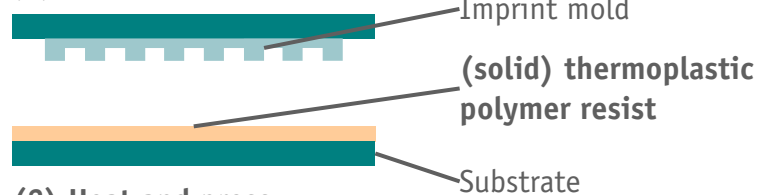


Modern days

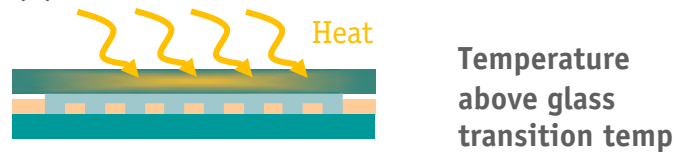
Basic principle of nanoimprint lithography

THERMAL NIL

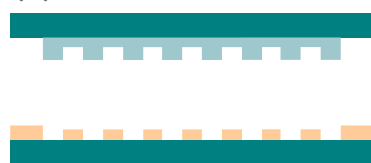
(1) Resist coating



(2) Heat and press



(3) Cool and separate



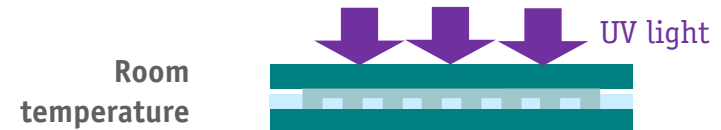
VS

UV NIL

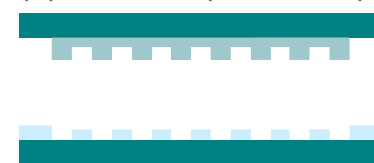
(1) Resist coating



(2) Expose and press



(3) Separate (no cooling)



Basic principle of nanoimprint lithography

THERMAL NIL

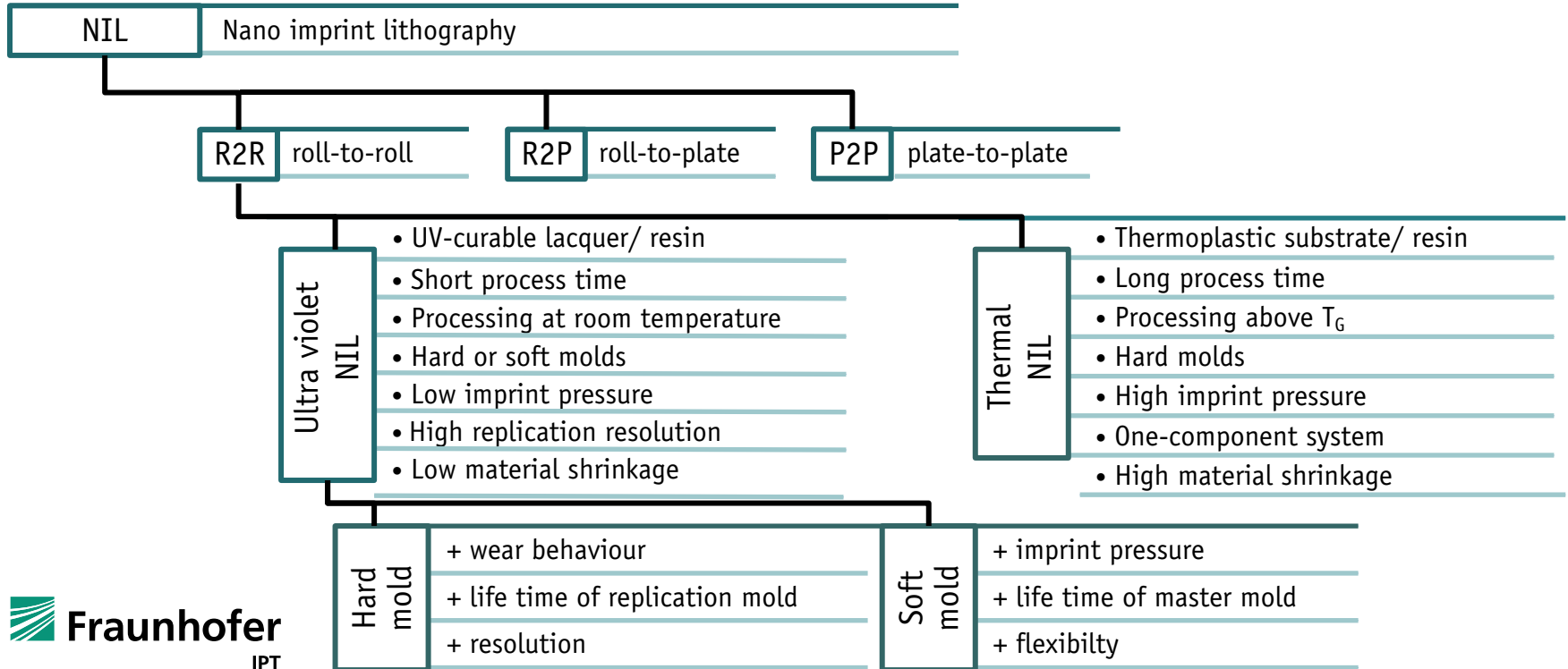
VS

UV NIL

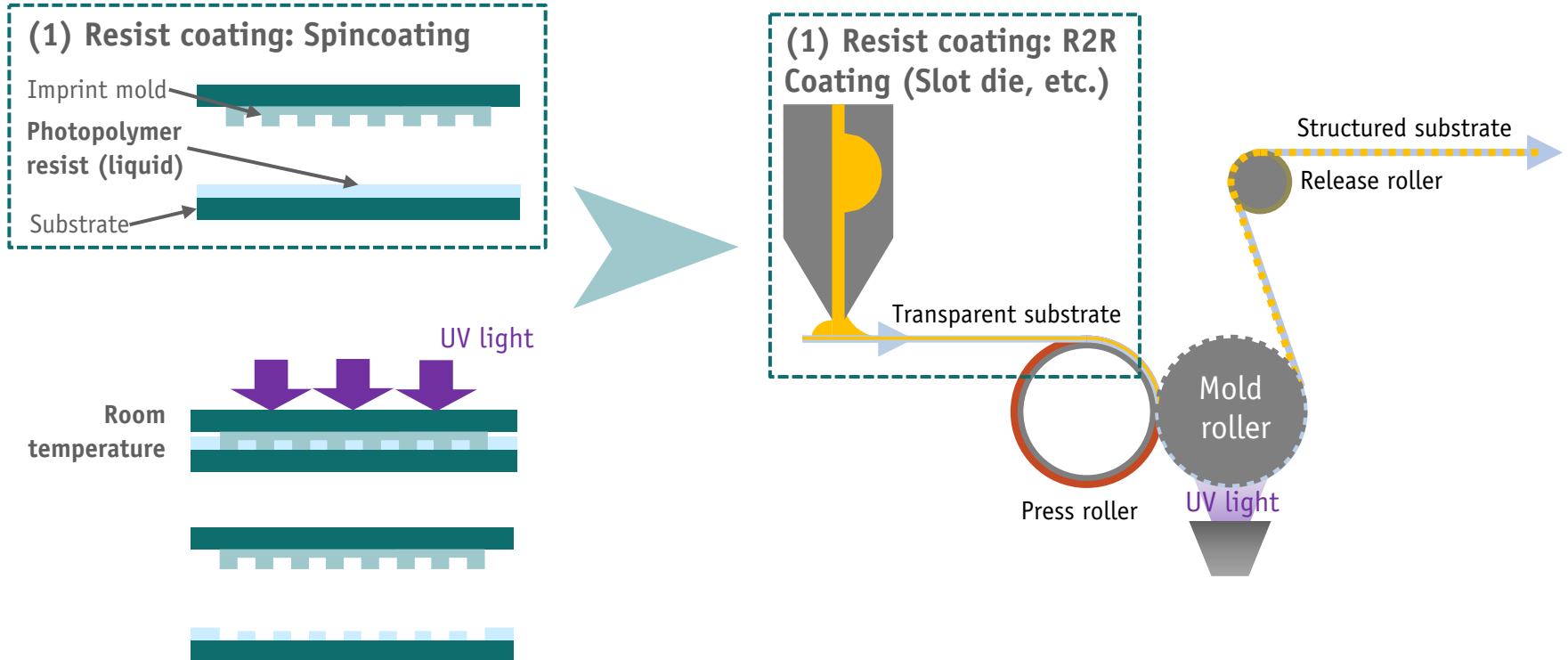
- ✓ **Imprint into substrate possible**
- ✓ **Great depths possible**
- ✓ (slower)
- ✓ heat distribution
- ✓ Thermal conductive mold
- ✓ Thermal expansion of mold and resist
- ✓ Cooling
- ✓ Higher pressure

- ✓ (faster)
- ✓ **Uniformity**
- ✓ **Less viscous resists**
(less pressure)
- ✓ **Soft molds possible**
- ✓ UV resists
(Transparent substrate or mold)

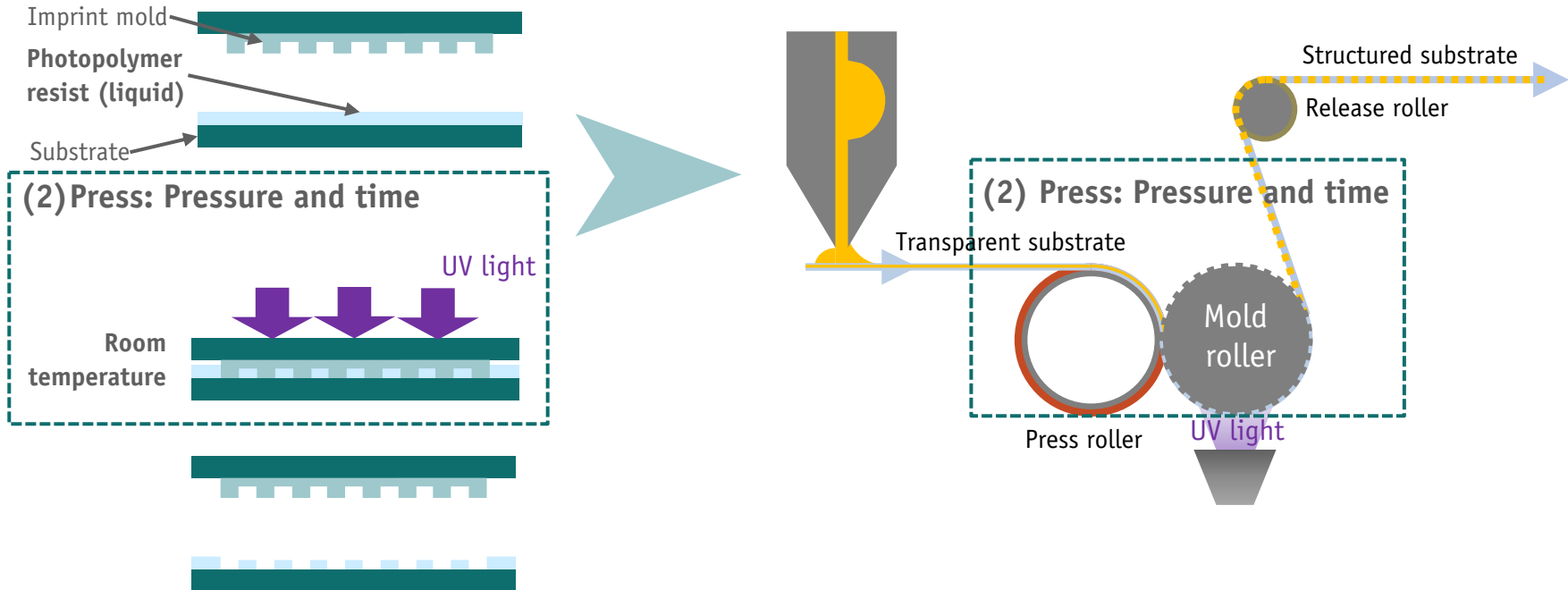
Overview of nanoimprint lithography technologies and processes



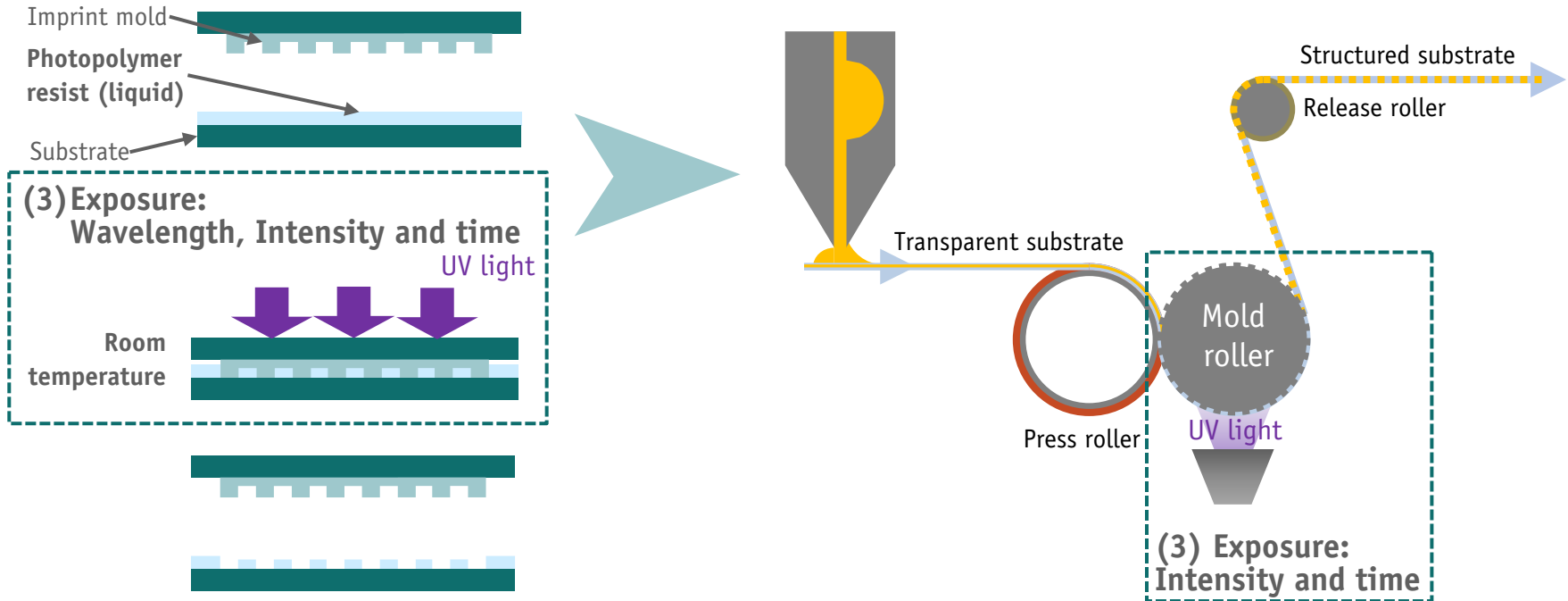
Translating from P2P to R2R



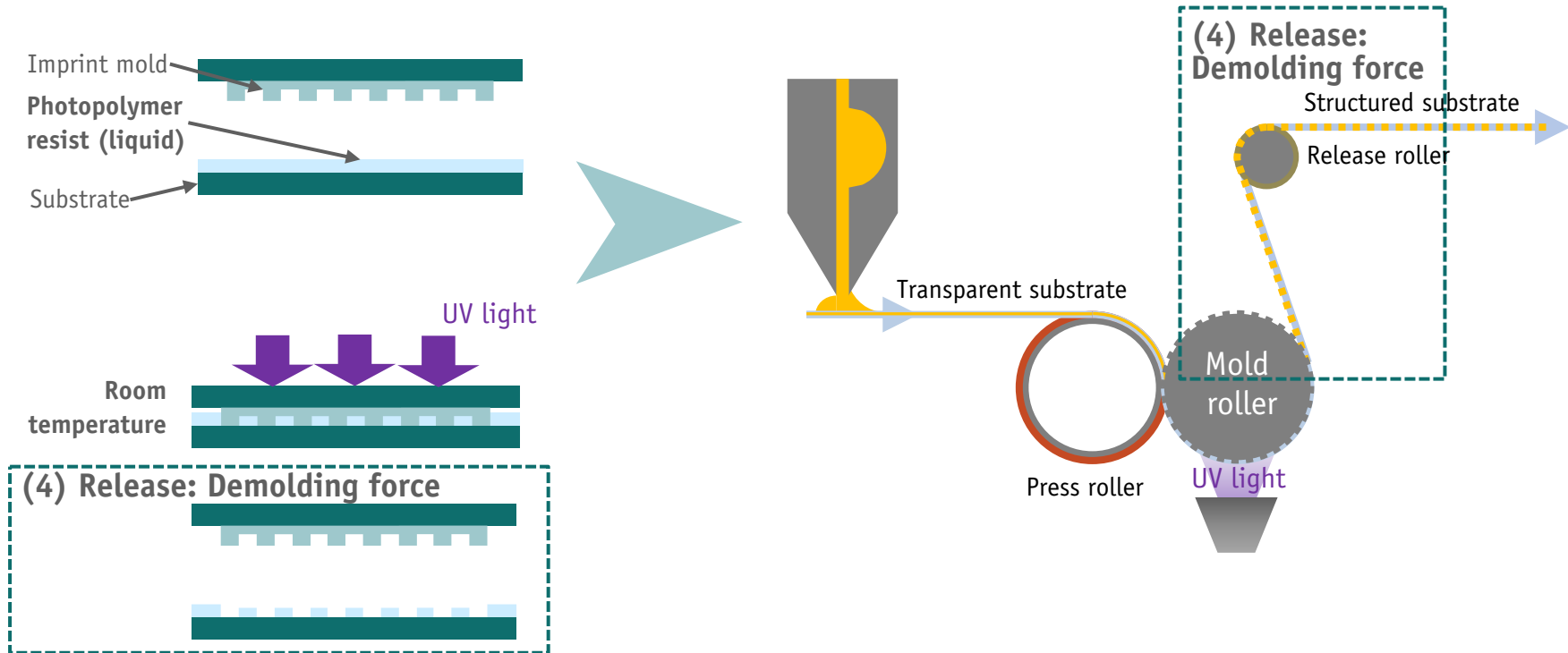
Translating from P2P to R2R



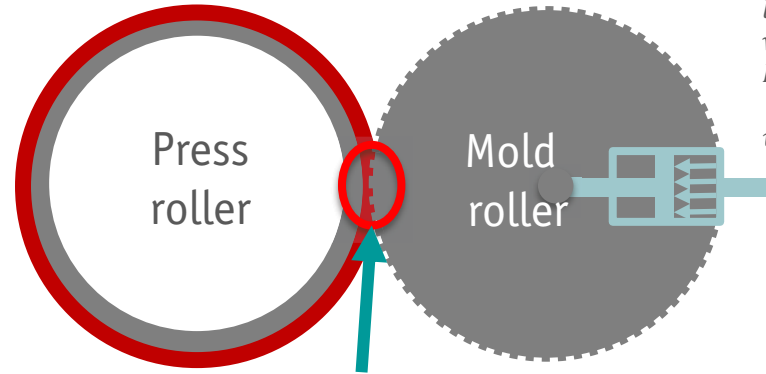
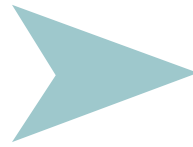
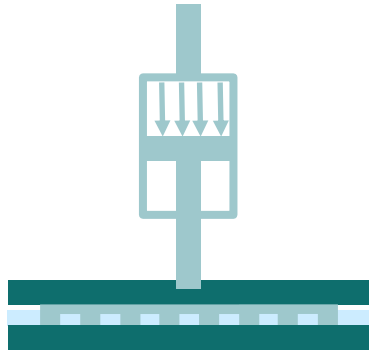
Translating from P2P to R2R



Translating from P2P to R2R



Translating from P2P to R2R



F: Force mold roller
r: Radius press roller
l: length press roller
v: Poisson's number
E_{comb}: Combined modulus
v_{web}: Webspeed

Hertzian deformation:

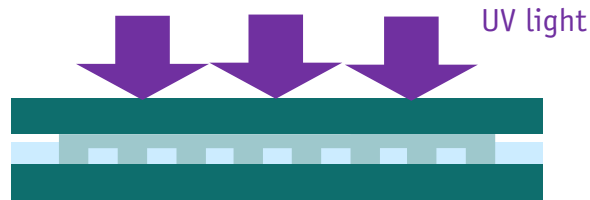
$$p_{\text{press}} = p_{\text{cylinder}} \cdot \frac{A_{\text{cylinder}}}{A_{\text{imprint}}}$$

$$t_{\text{press}} = \text{variable}$$

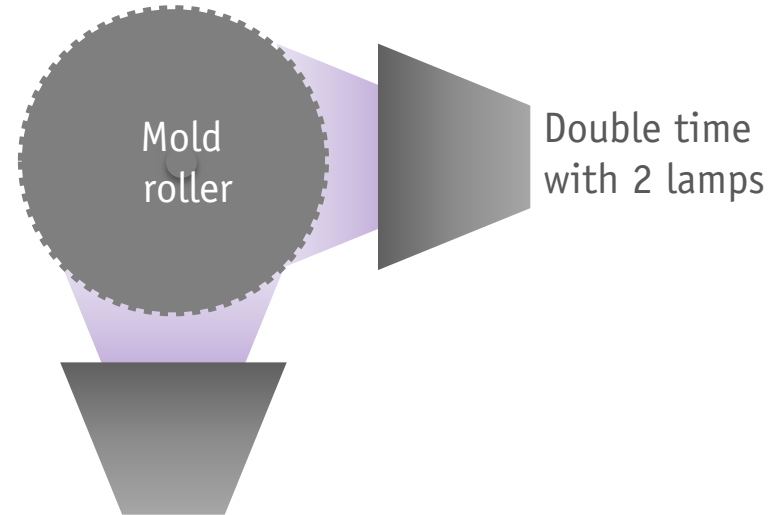
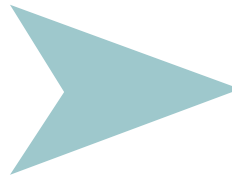
$$p_{\text{max}} = \sqrt{\frac{F}{2\pi r l} \cdot \frac{E_{\text{comb}}}{1 - v^2}}$$

$$t_{\text{press}} = 2 \cdot \arcsin \left(1 - \sqrt{\frac{F}{2\pi r l E_{\text{comb}}} \cdot \frac{1}{1 - v^2}} \right) \cdot \frac{r}{V_{\text{web}}}$$

Translating from P2P to R2R



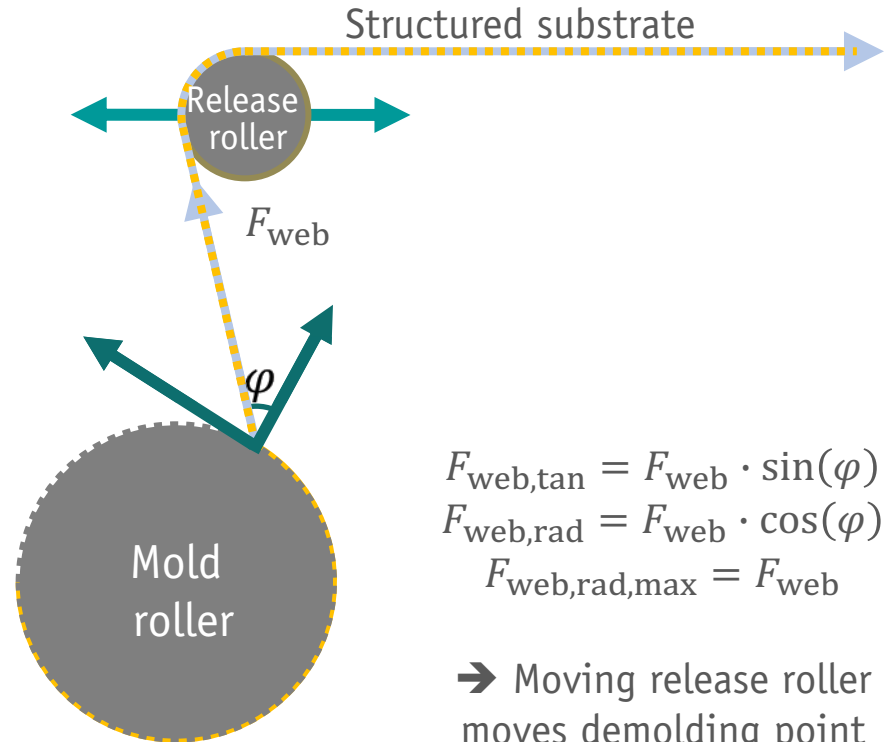
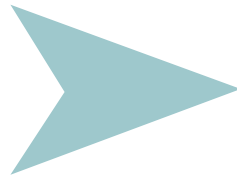
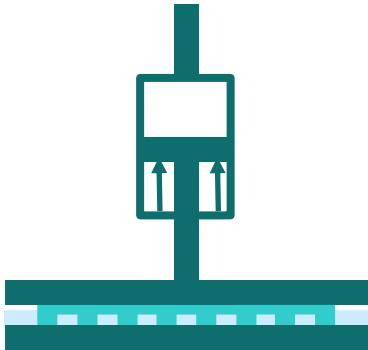
$$t_{\text{expo}} = \text{variable}$$
$$I = I_0 \cdot e^{-\alpha \cdot d_{\text{resist}}}$$



$$t_{\text{expo}} = \frac{2r}{v_{\text{web}}} \cdot \arcsin\left(\frac{w_{\text{lamp}}}{2r}\right)$$
$$I = I_0 \cdot e^{-\alpha \cdot d'_{\text{resist}}}$$
$$\text{with } d' = \sqrt{(r + d)^2 - x^2} - \sqrt{r^2 - x^2}$$

Translating from P2P to R2R

$$p_{\text{release}} = p_{\text{cylinder}} \cdot \frac{A_{\text{cylinder}}}{A_{\text{imprint}}}$$

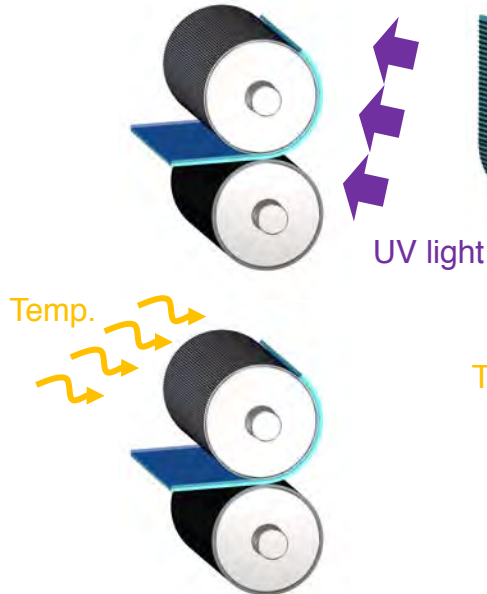


Translating from P2P to R2R

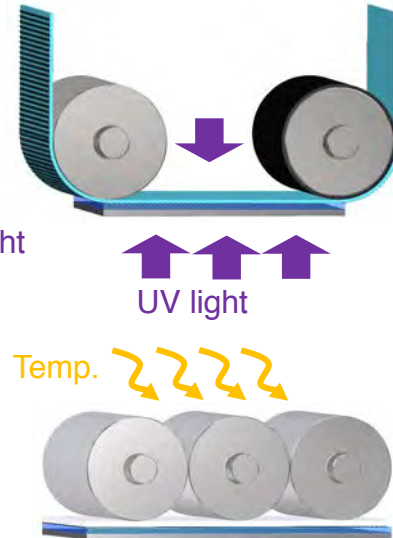
Parameter	P2P (lab)	R2R (1 m/min)
Coating thickness	5 μm (Spin coating)	5 μm (Slot die)
Dimensions	25 x 25 mm ²	250 mm
Press pressure	1 bar	Up to 3.6 bar
Press time	2 s	~3 s (increase with softer press roller)
Exposure time	4 s	~6.4 s (1 lamp)
Release force	15 N	~120 N
Release angle to normal	0°	53° (@200 N)
Tensile force	-	Up to 250 N
Throughput	3 samples/minute (0.001875 m ² /min)	0,25 m ² /min Factor >120

Technologies and processes

R2R



R2P



UV NIL system designs:

- ✓ Surface activation
Corona, plasma, chemical treatment
- ✓ Coating
Slot die, knife, roller coater ...
- ✓ UV curing
Mercury, LED UV radiator

NIL system designs:

- ✓ Heating
- ✓ IR/ NIR, inductive, laser heating or heated fluids in embossing drum

Replication mold:

- ✓ Drum, endless belt, film
- ✓ One-/ Multi-Temperature zones

Technologies and processes

Process parameters (selection):

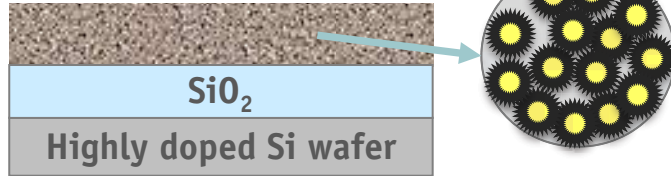
- ✓ Resist
 - ✓ Chem. formulation
 - ✓ Viscosity / rheology
- ✓ Film
 - ✓ Chem. formulation
 - ✓ Chemical / mechanical pre-treatment
- ✓ Tool
 - ✓ Hard / soft mold
 - ✓ Anti-adhesion layer
- ✓ UV-source
 - ✓ Spectral distribution
 - ✓ LED- / conventional source



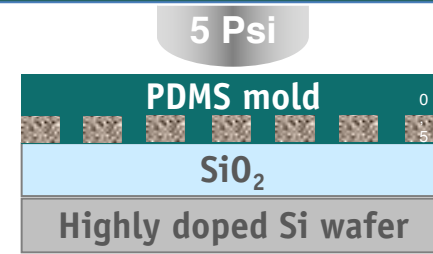
Innovative coating of gold contacts:

A. Coating of substrate

Nanoparticle solution



B. Thermal imprint



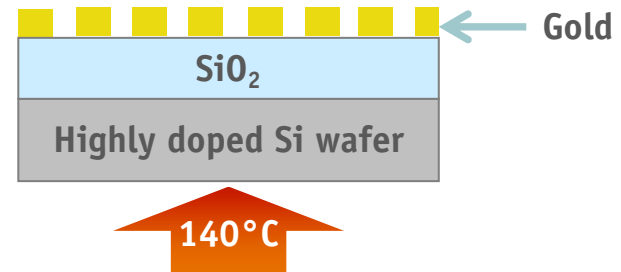
80°C

C. Imprinted structure

Dried nanoparticles

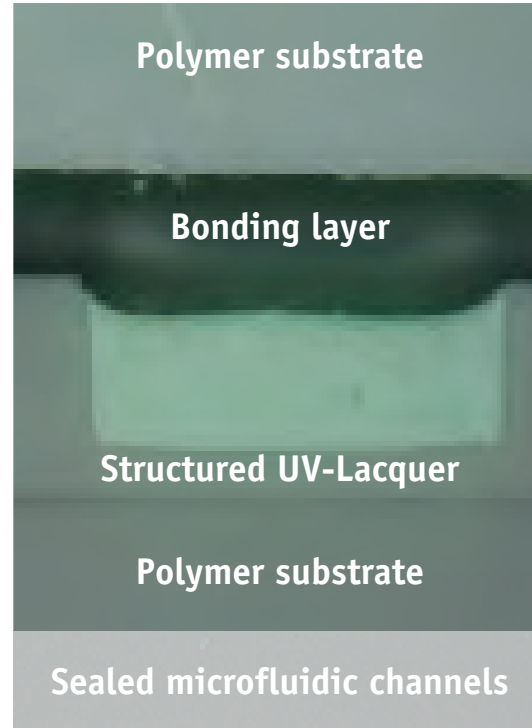
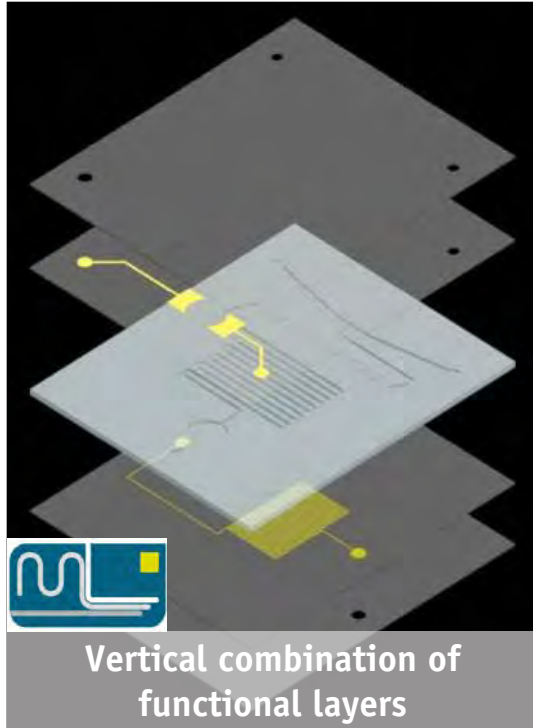


D. Sintering of gold NP to gold-contacts



140°C

Technologies and processes



1. Top sealing layer
2. Optical layer
 - ✓ light guide for fluorescence detection
3. Microfluidic layer
 - ✓ Fluid input, mixer, serpentine channel, detection well
4. Electrical layer
 - ✓ Heaters for two temperature zones
5. Bottom sealing layer

2 stacked imprint structures

Technologies and processes

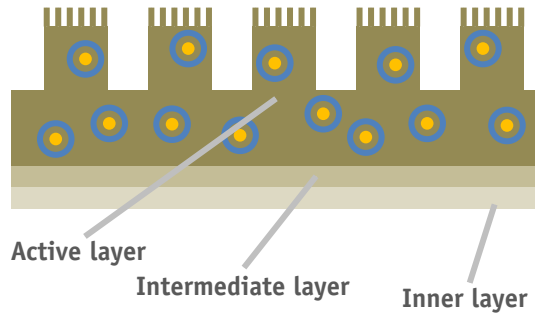
Micro pillars:

✓ Anti-sticking properties

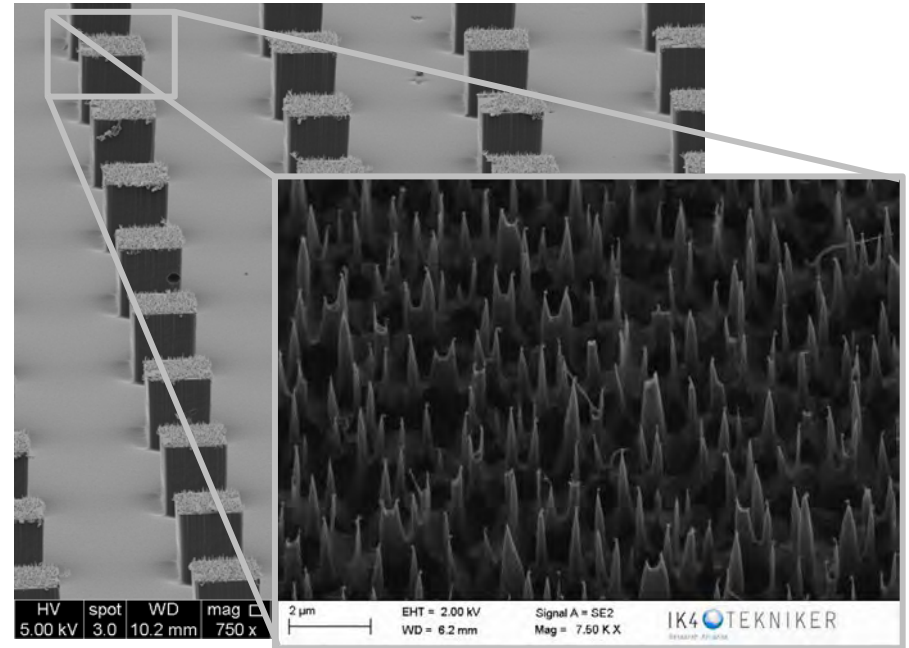
Nanospikes:

✓ Perforation

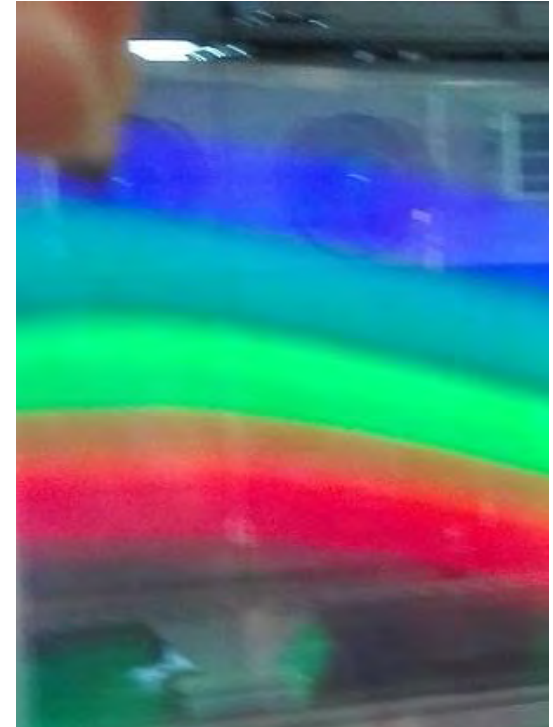
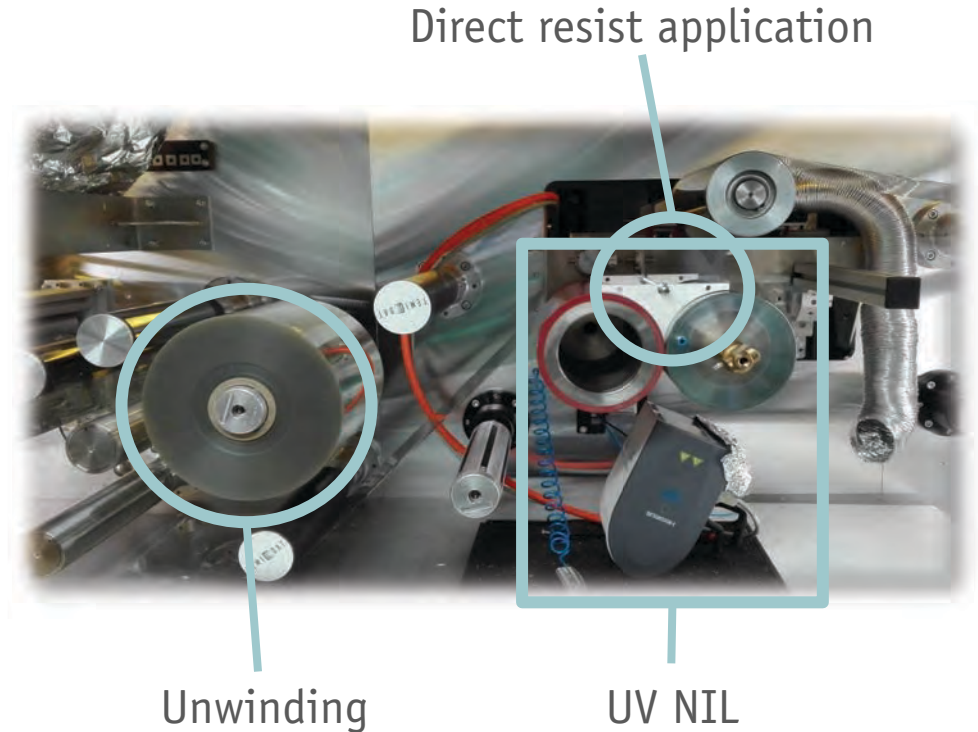
3-layered antimicrobial film



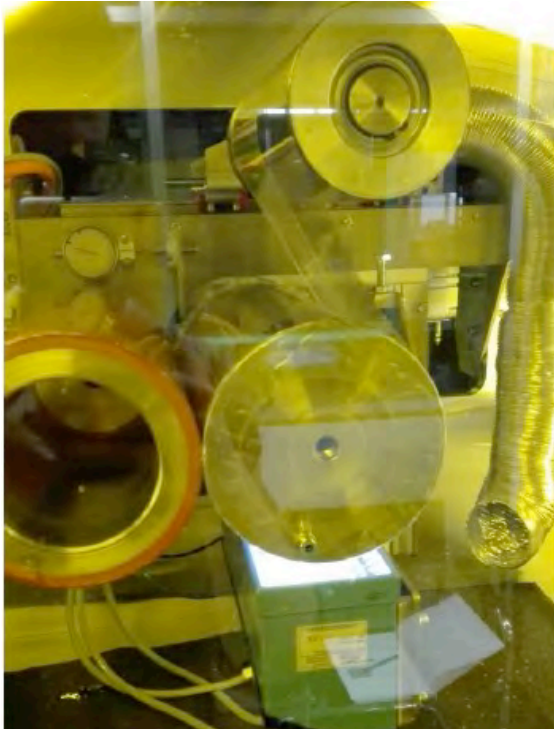
Hierarchical micro-/ nano structures



Technologies and processes

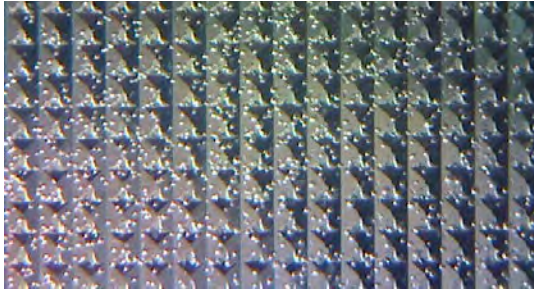


How to not do UV NIL:

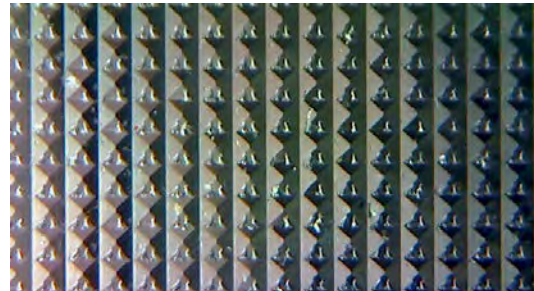


- ✓ Too much resist
- ✓ Too little UV
- ✓ Too fast substrate speeds

Technologies and processes



Bubble enclosures



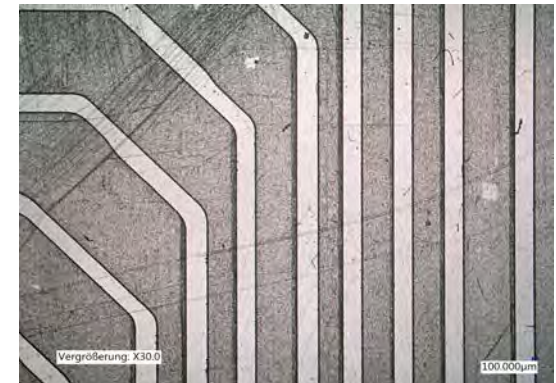
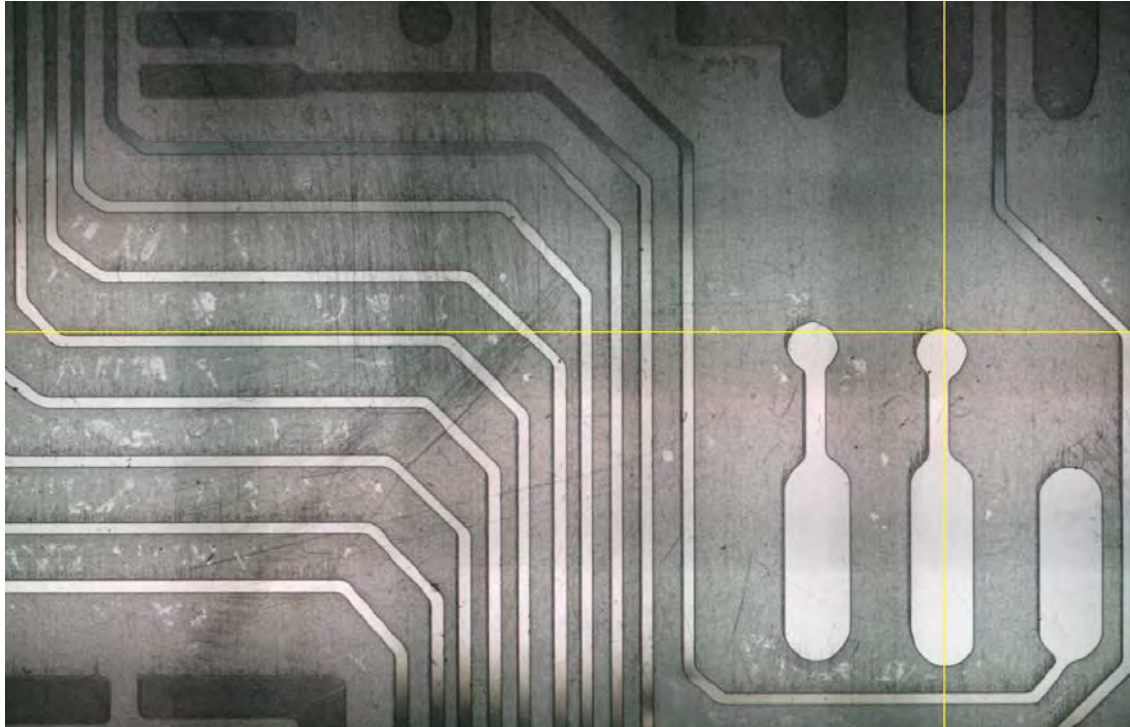
Geometrical defects

Influences on the quality mainly result from
Substrate: ✓ Impurities / Dust

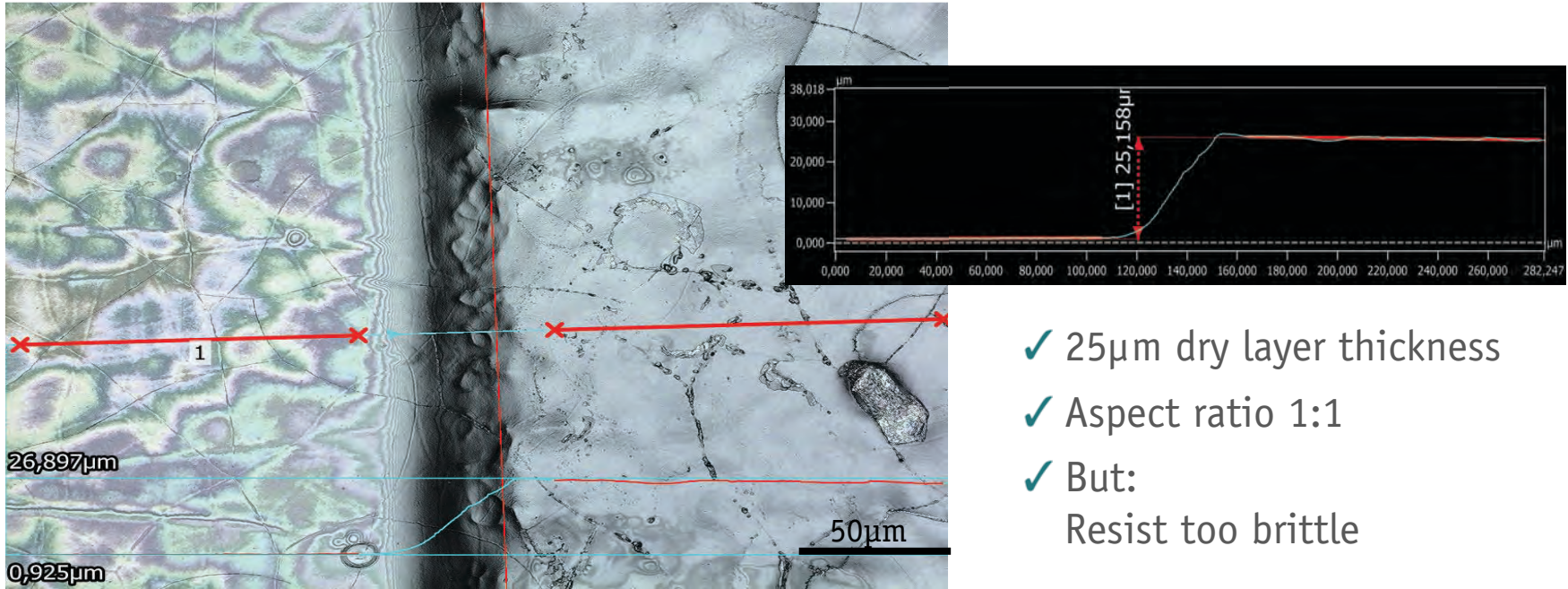
Wetting behaviour
Embossing drum: ✓ Machining errors
(e.g. badly joint sleeves)
✓ Wear

Partial / total lacquer adhesion
Resist: ✓ Impurities / Dust
✓ Bubbles / Foam
✓ Coating homogeneity

Successful imprint several mm down to 40µm feature size

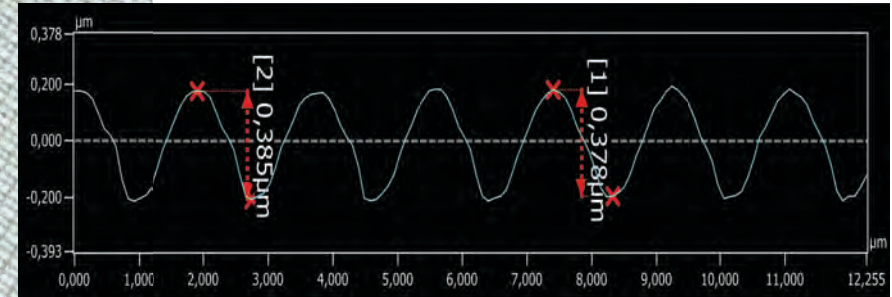
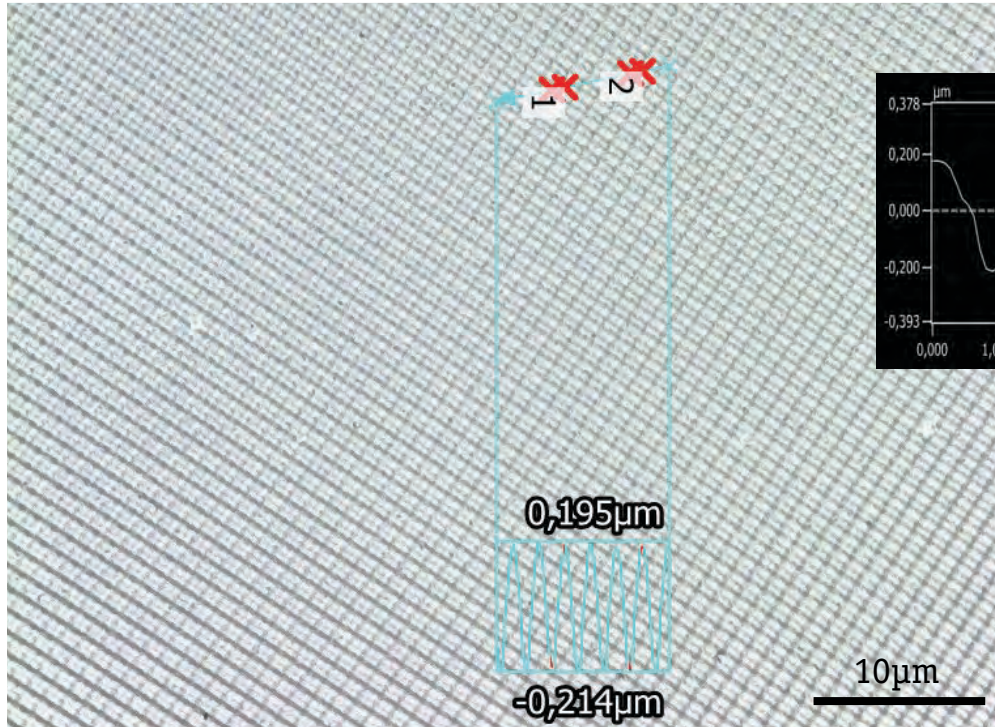


Technologies and processes



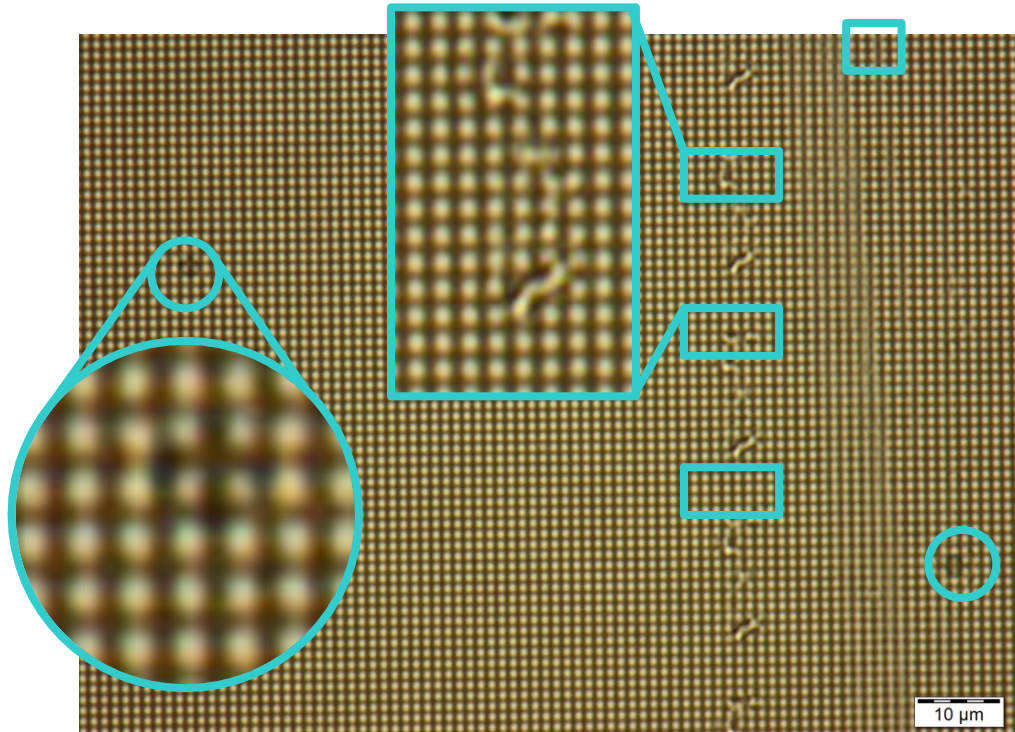
- ✓ 25µm dry layer thickness
- ✓ Aspect ratio 1:1
- ✓ But:
Resist too brittle

Technologies and processes



- ✓ 380nm feature size
- ✓ Aspect ratio 2:1
- ✓ Low density of defects

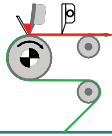
Technologies and processes



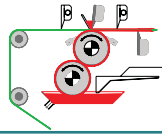
Imprint defects:

1. Surface scratches
2. Point defects
→ No effect on optical purpose
3. Damages in sleeve
→ Periodic damage in optical structure

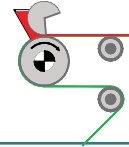
Coating systems



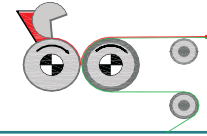
Knife system



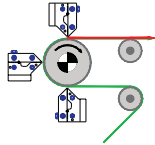
Double side system



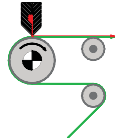
Commabar system



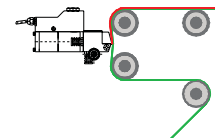
Reverse commabar system



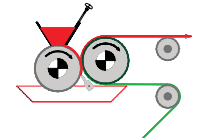
Slot die system



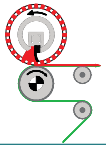
Curtain coating system



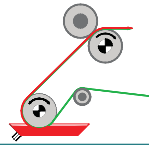
Hotmelt slot die system



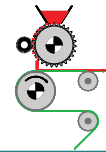
Case knife system



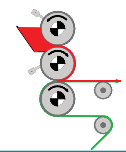
Rotary screen system



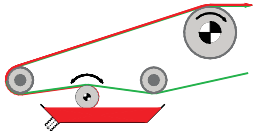
Dipping system (Foulard)



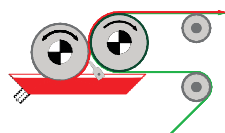
Powder scattering system



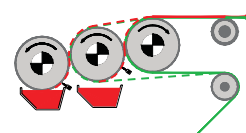
Reverse roll system



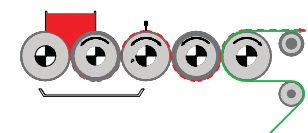
Micro roller system



2 Roller system

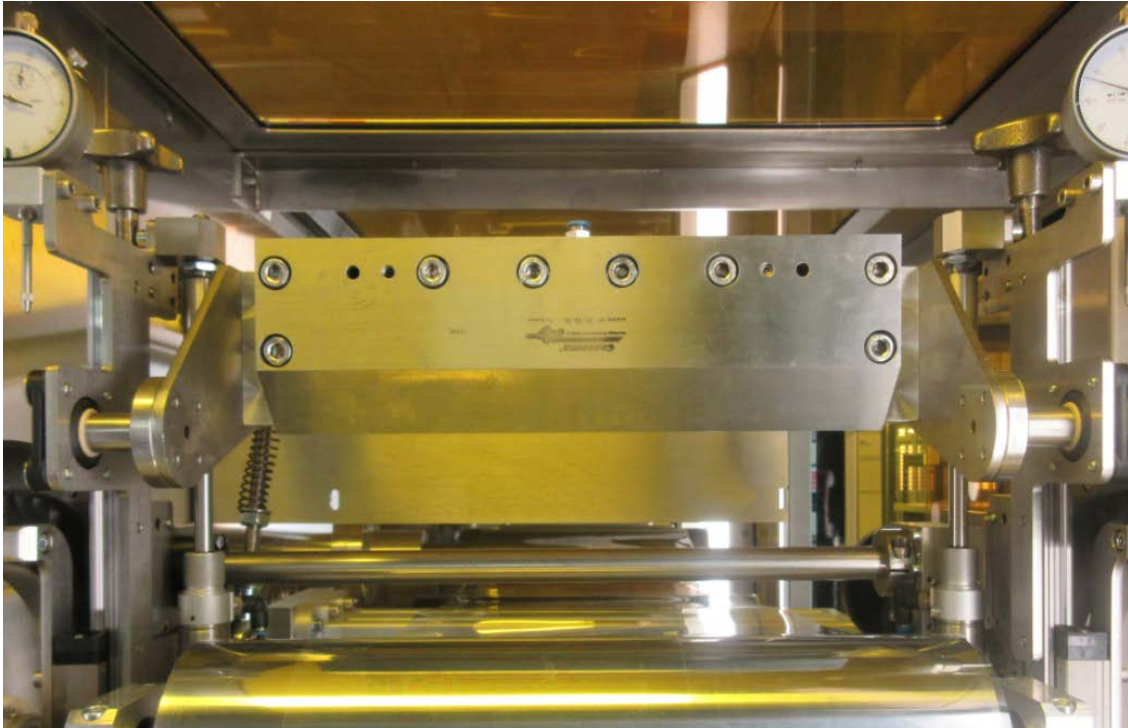


3 Roller combi system

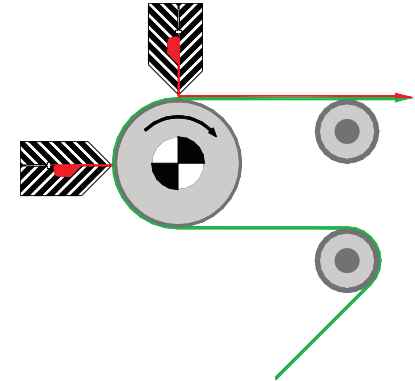


5 Roller system

Coating and printing for nanoimprint lithography

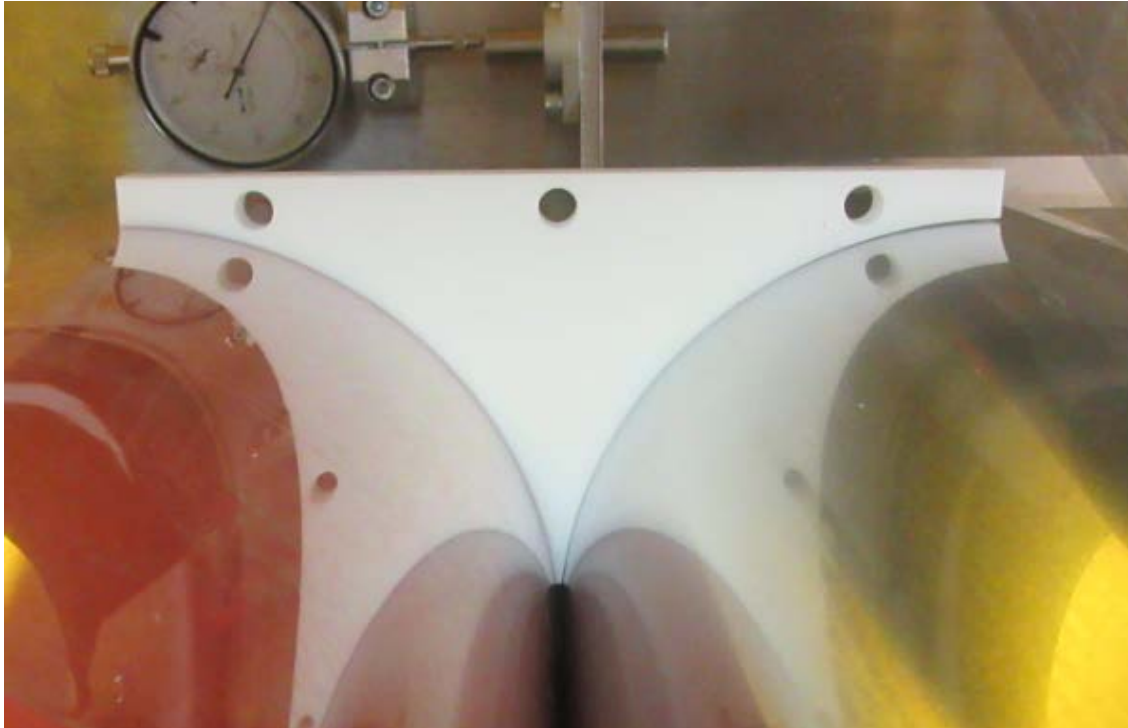


Slot die coating for
pre-metered film coating

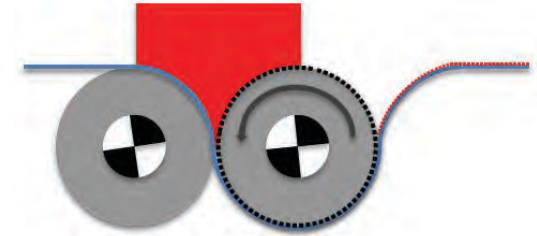


- ✓ Layer control
- ✓ Level control in the nip
- ✓ 12/9" position

Coating and printing for nanoimprint lithography



Nip coating

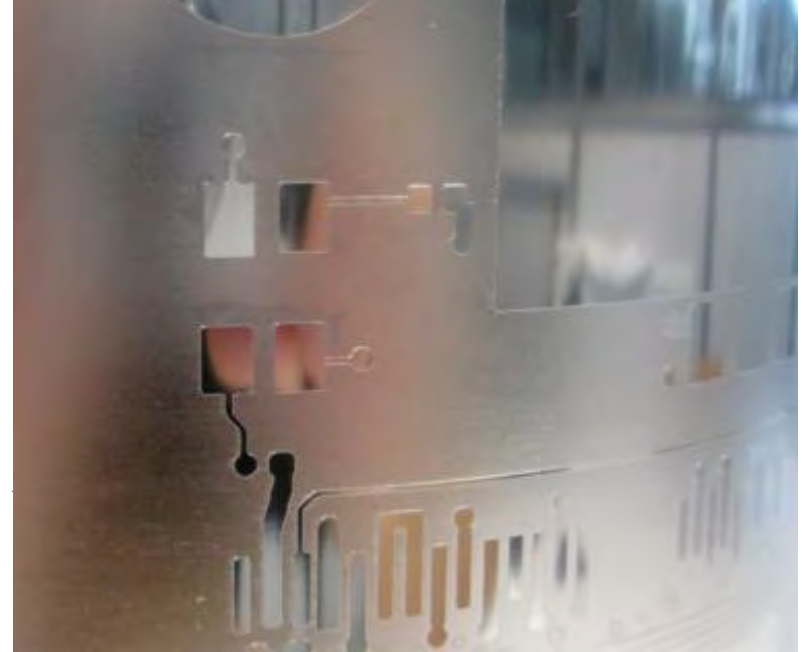


- ✓ Layer control by gap
- ✓ Level control in the nip
- ✓ Compact process

Coating and printing for nanoimprint lithography

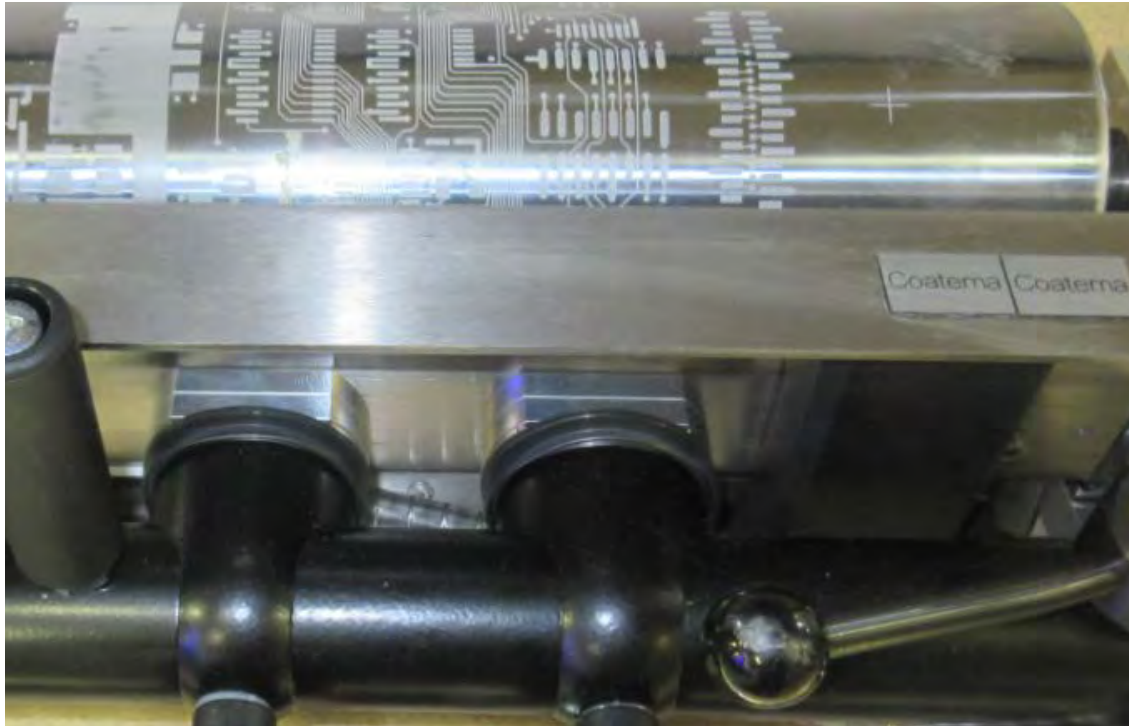


Homogeneous structure

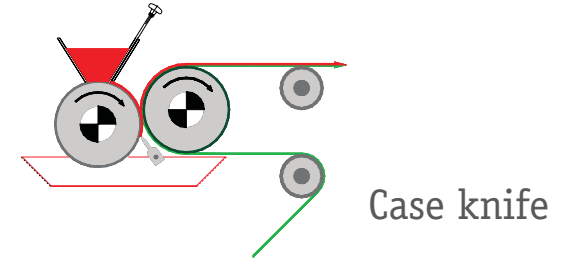


Inhomogeneous structure

Coating and printing for nanoimprint lithography



Printing for inhomogeneous structures?

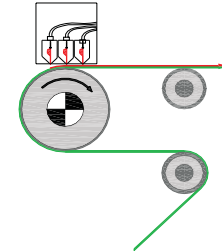


- ✓ Layer control „inhomogeneous“
- ✓ Matched level control in the nip
- ✓ Nip material fits „sleeve consumption“

Coating and printing for nanoimprint lithography



Printing for inhomogeneous structures?



Inkjet

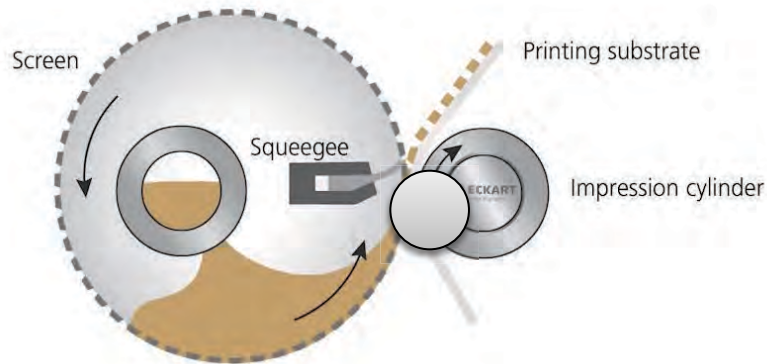
- ✓ Layer control „inhomogeneous“
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Coating and printing for nanoimprint lithography

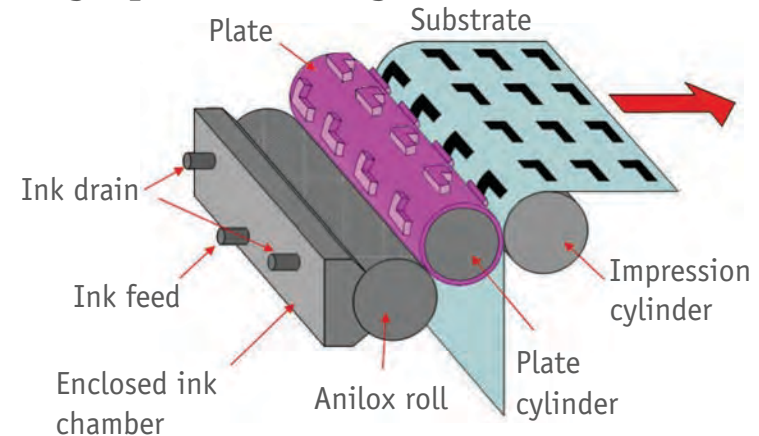
Printing for inhomogeneous structures?

- ✓ Layer control „inhomogeneous“
- ✓ Matched level control in the nip
- ✓ Nip material fits „sleeve consumption“

Rotary Screen Printing



Flexographic Printing



Summary

Introduction

Technologies
and processes

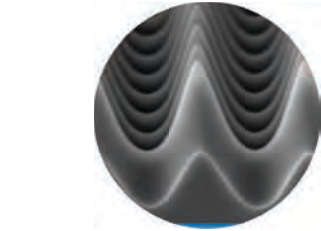
Products

Equipment

Summary

Products

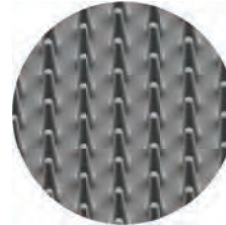
Applications



Display



Photonics



Bionics



Life science



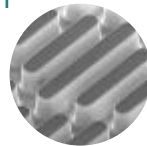
Printed electronics



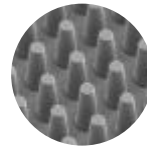
Retroreflectors



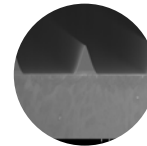
Diffractive optical elements



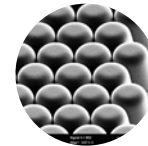
Antibacterial surfaces



Super hydrophobic surfaces



Shark skin



Haptic surfaces



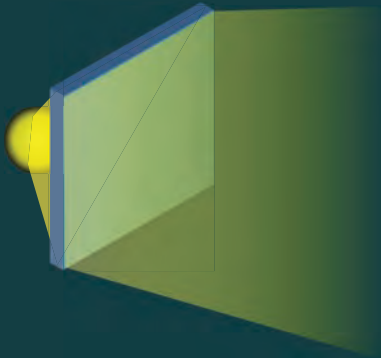
Microfluidic structure

Products

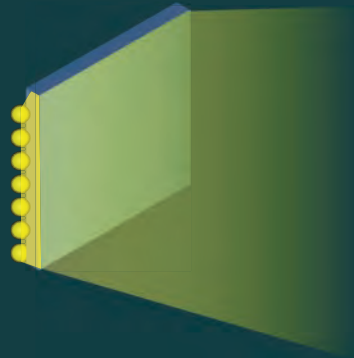


Products

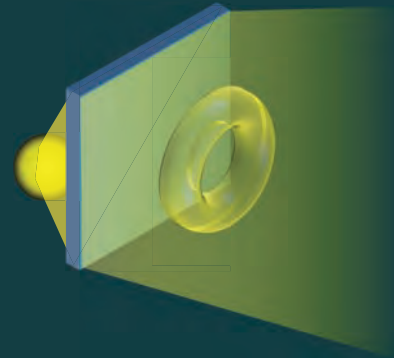
temilux® T0
Transmission optics



temilux® LG
Lightguide solutions



temilux® 3D
3D lighting effects



More ideas: PrintoCent Designer's Handbook

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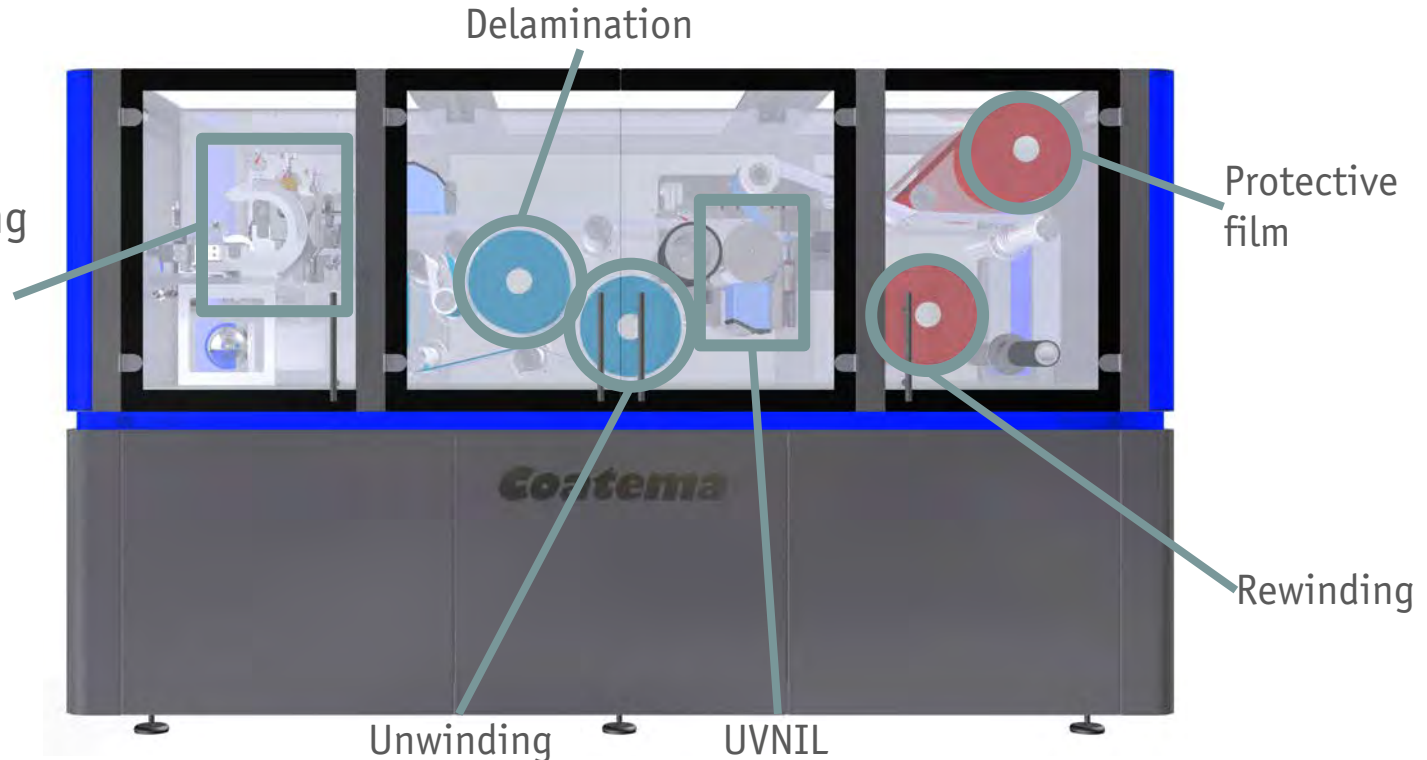
Summary

Equipment

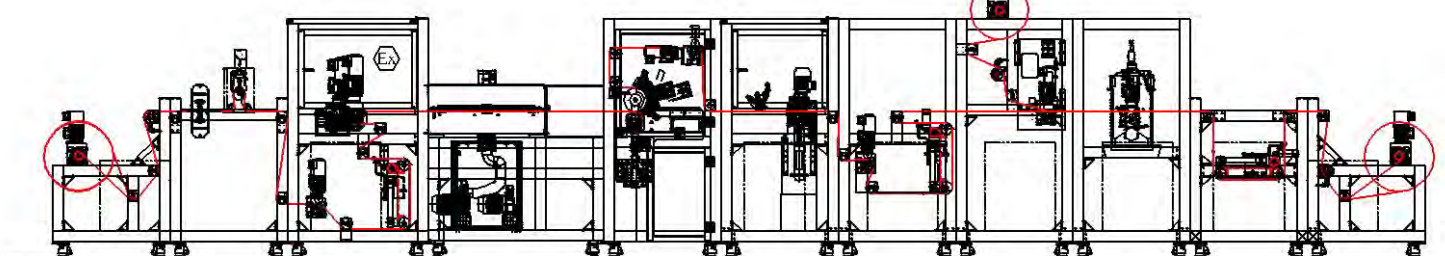
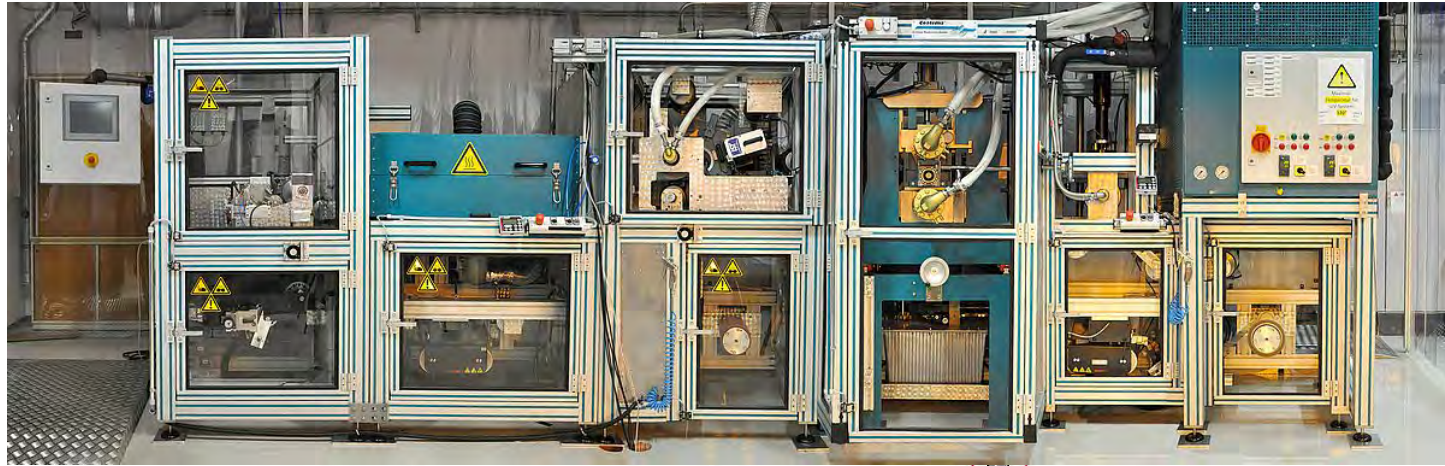
Equipment

Coating Unit:

- ✓ Knife coating
- ✓ Slot die coating
- ✓ Inkjet
- ✓ Flexographic printing
- ✓ Rotary screen printing



Equipment



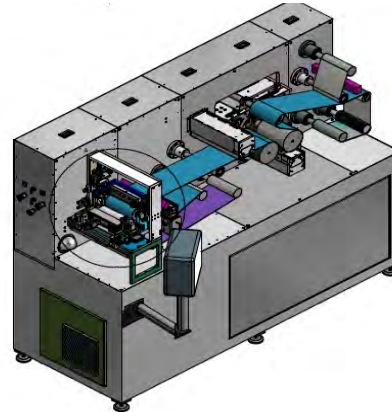
Equipment



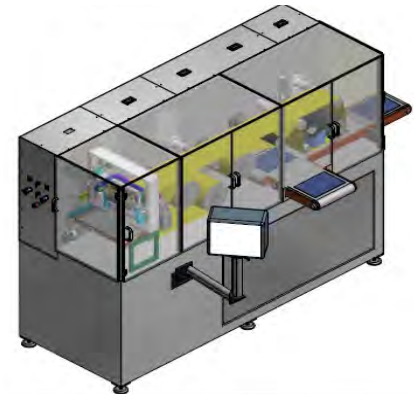
Temicoat
Test Solution S2S



Temicoat
Test Solution R2R



Temicoat
NIL 300 R2R



Temicoat
NIL 300 R2P

Equipment

R2R + R2P-Machine for Temicon

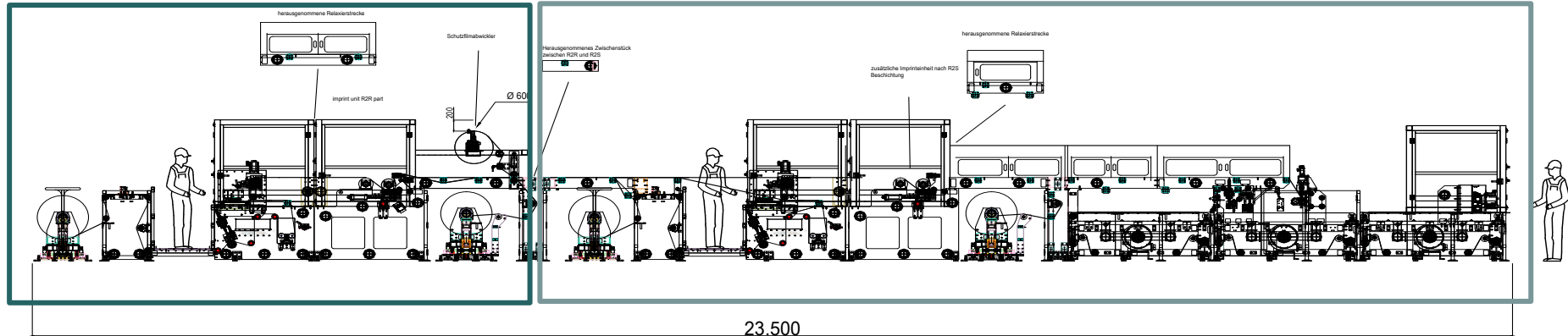
Specs:

Working width R2R: 1100 mm

Dimensions R2P: 1000 mm x 1600 mm

Speeds: 6 – 60 m/min

Coating unit: Slot die coating



Summary

Introduction

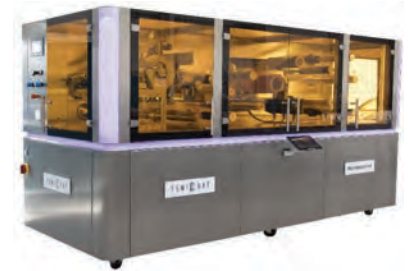
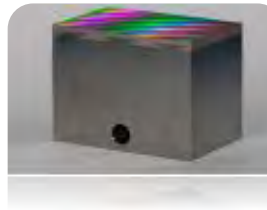
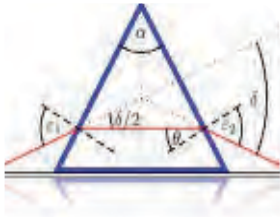
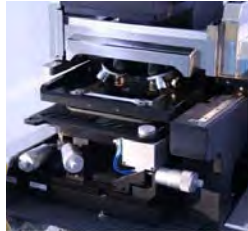
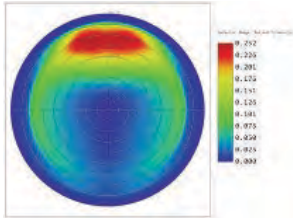
Technologies
and processes

Products

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Summary

Summary



Simulation

Origination

Tooling

Replication

Do not hesitate to contact us!



Anything missing?

Let us know and we will make it happen!

Our R&D centre is worldwide the most versatile centre for coating, printing and laminating.

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sales@coatema.de

Thank you



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